Exhibit A

Semiconductor Terminology
Graphic Glossary of Terms

Michael Heynes, Ph.D.
Anne K. Miller

REWORK:
Out-of-specification wafers that are sent through a process again.

Inspection

Fabrication Processes ← Rework → Good / Scrap

REWORK RATE:
The percentage of wafers requiring rework.

Rework Rate =

$$\frac{\#\ \text{Reworked Wafers}}{\#\ \text{Wafers started in process step}} \times 100\ \%$$
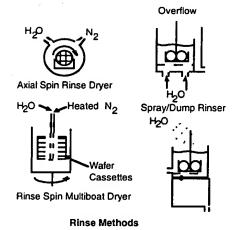
RF:
See "Radio Frequency".

RF HEATING:
See "Radio Frequency Heating".

RIE:
See "Reactive Ion Etch".

RINSE:
The removal of cleaning solutions, etchants or developers etc. from the wafer using water. This process stops the processes by removing the active chemical from the surface. There are several different methods of rinsing: overflow rinsing, dump rinsing, and spin/rinse drying.

H_2O N_2
Axial Spin Rinse Dryer

Overflow
H_2O
Spray/Dump Rinser

H_2O Heated N_2
Wafer Cassettes
Rinse Spin Multiboat Dryer

H_2O

Rinse Methods